

Supporting Information

Efficient electrocatalytic conversion of CO₂ to syngas for Fischer-Tropsch process by partially reduced Cu₃P nanowire

Bing Chang^a, Xia-Guang Zhang^b, Zhaojun Min^b, Weiwei Lu^c, Zhiyong Li^b, Jikuan Qiu^b, Huiyong Wang^b, Jing Fan^{a*}, and Jianji Wang^{b*}

^a School of Environment, Key Laboratory for Yellow River and Huai River Water Environment and Pollution Control, Ministry of Education, Henan Normal University, Xinxiang, Henan, 453007, People's Republic of China

^b School of Chemistry and Chemical Engineering, Key Laboratory of Green Chemical Media and Reactions, Ministry of Education, Henan Normal University, Xinxiang, Henan, 453007, People's Republic of China

^c School of Chemical Engineering and Pharmaceutics, Henan University of Science and Technology, Luoyang, Henan, 471023, People's Republic of China

* Corresponding authors

E-mail address: fanjing@htu.edu.cn (Prof. J. Fan) and jwang@htu.edu.cn (Prof. J. Wang)

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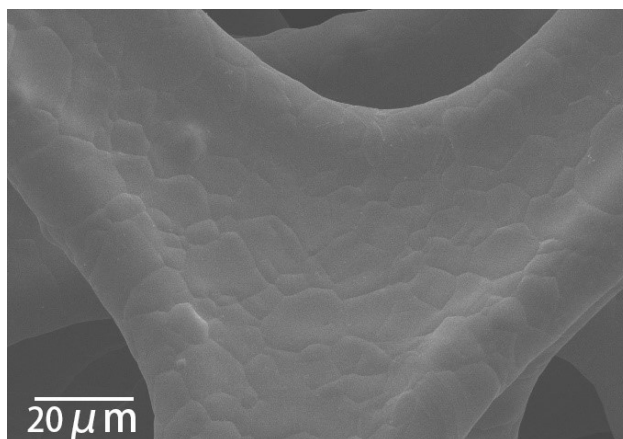


Fig. S1. SEM image of the bare copper foam.

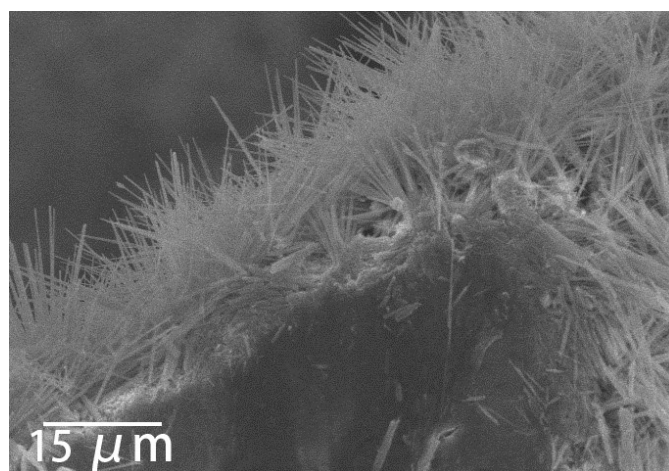


Fig. S2. Cross-section SEM image of the R-Cu₃P/Cu.

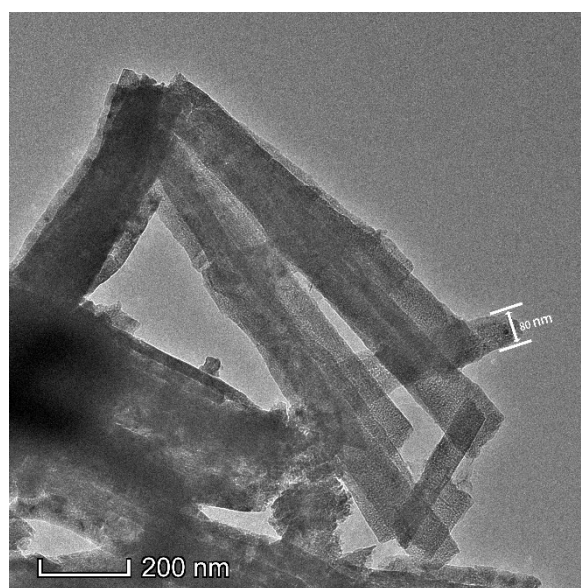


Fig. S3. TEM image of the R-Cu₃P/Cu.

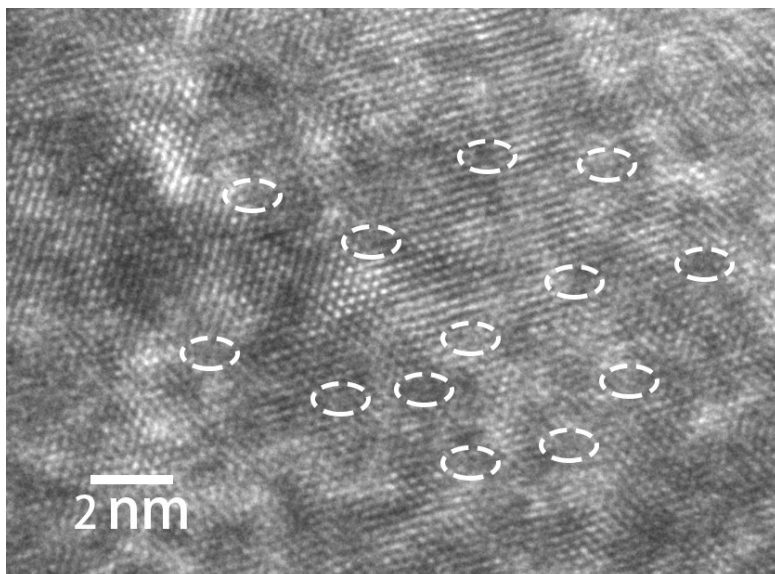


Fig. S4. HR-TEM partial enlarged image of R-Cu₃P/Cu.

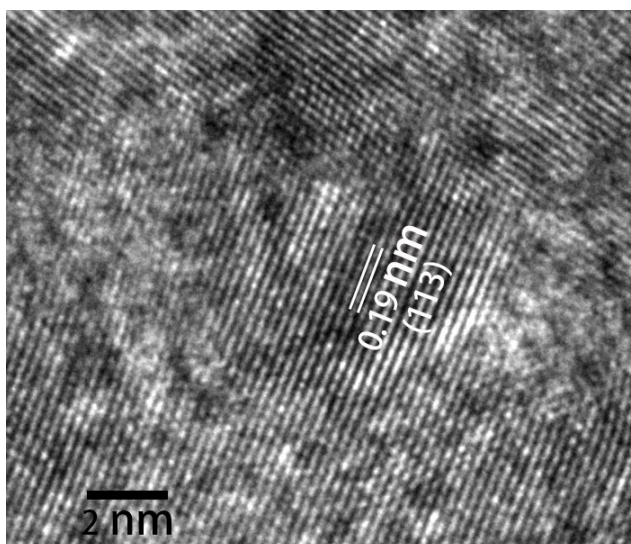


Fig. S5. HR-TEM image of the Cu₃P/Cu.

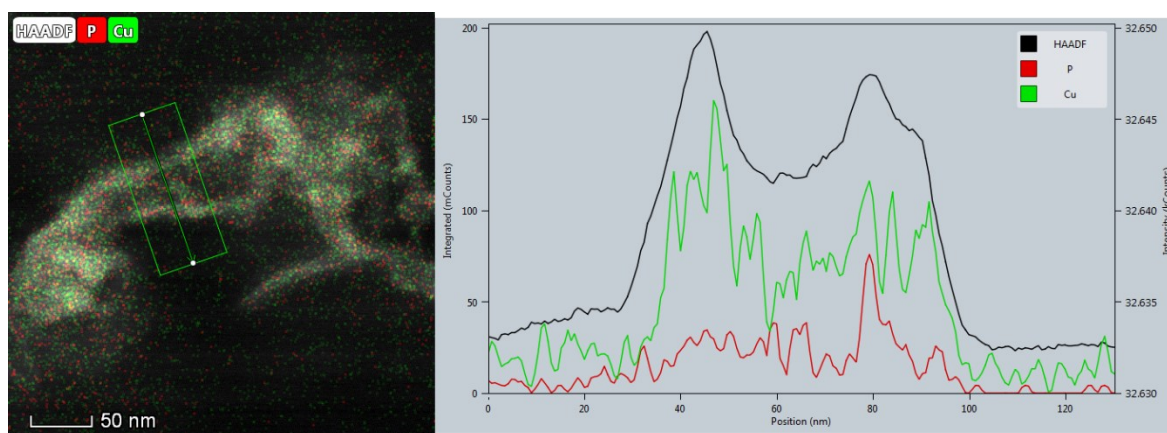


Fig. S6. HAADF image and corresponding EDS line scanning spectrum of R-Cu₃P/Cu.

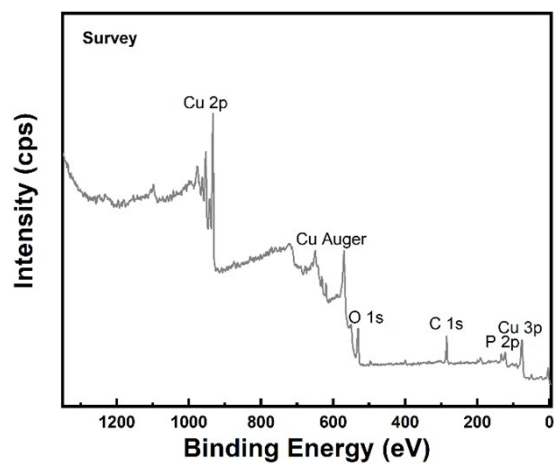


Fig. S7. XPS survey spectrum of R-Cu₃P/Cu.

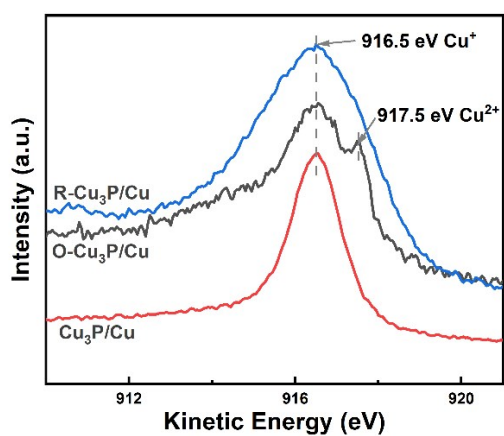


Fig. S8. AES spectra of Cu₃P/Cu, O-Cu₃P/Cu, and R-Cu₃P/Cu.

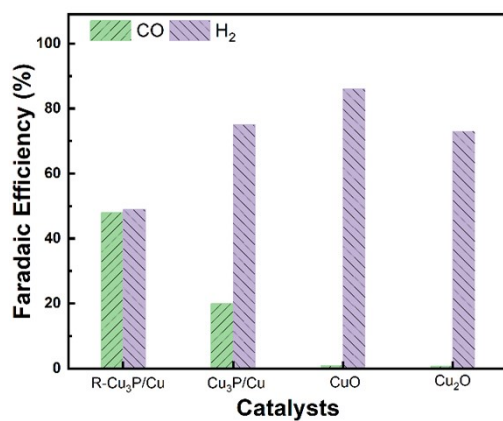


Fig. S9. CO and H₂ FE of R-Cu₃P/Cu, Cu₃P/Cu, CuO, and Cu₂O at -0.625 V vs. RHE.

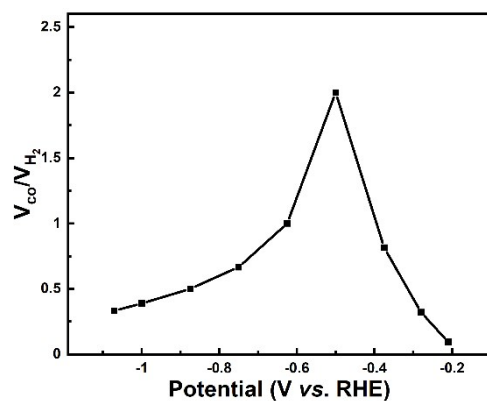


Fig. S10. The ratio of V_{CO}/V_{H_2} at different applied potentials.

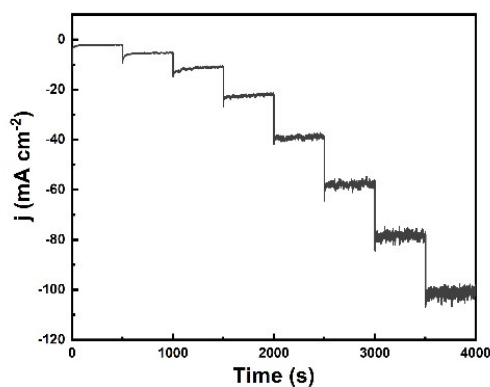


Fig. S11. Multi-potential process of R-Cu₃P/Cu in CO₂RR process. Each applied potential last for 500 s.

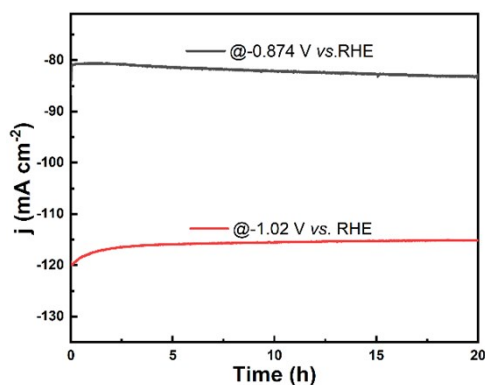


Fig. S12. Time-dependent current plots of R-Cu₃P/Cu in CO₂-saturated 0.5 M NaHCO₃ solution at preset potentials of -0.874 V (CO/H₂: 1/2) and -1.02 V (CO/H₂: 2/5).

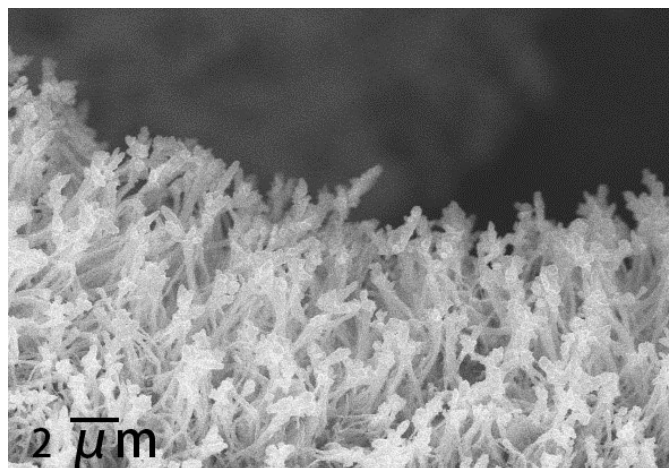


Fig. S13. SEM image of R-Cu₃P/Cu after 20 h potentiostatic electrolysis.

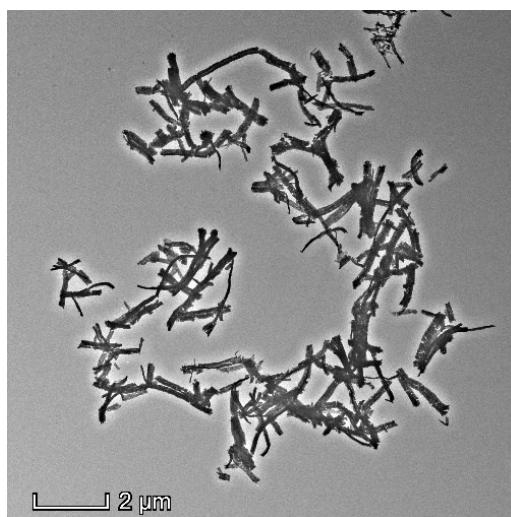


Fig. S14. TEM image of R-Cu₃P/Cu after long-term electrolysis.

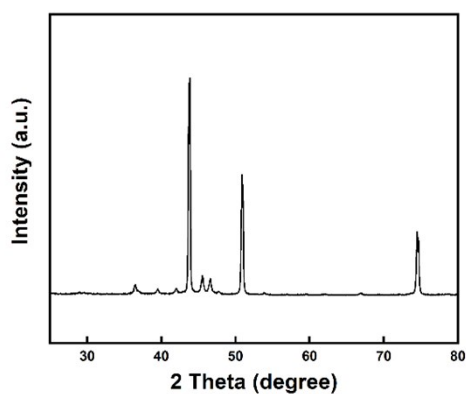


Fig. S15. XRD pattern of R-Cu₃P/Cu after long-term electrolysis.

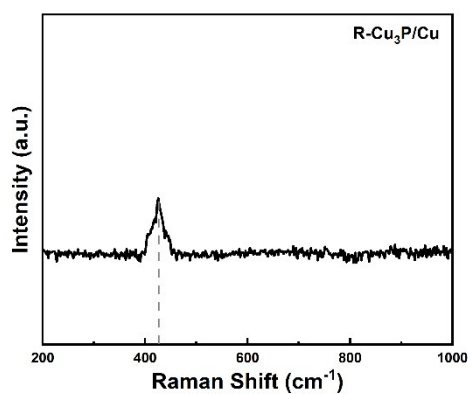


Fig. S16. Raman spectrum of R-Cu₃P/Cu after long-term electrolysis.

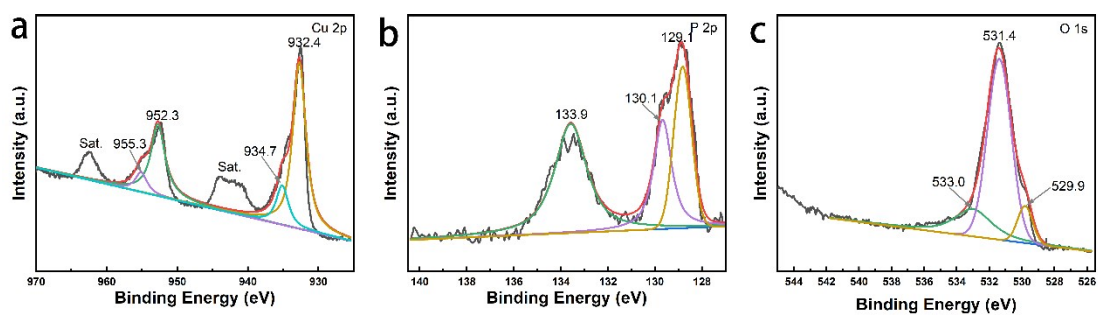


Fig. S17. High-resolution XPS spectra of R-Cu₃P/Cu after long-term electrolysis.

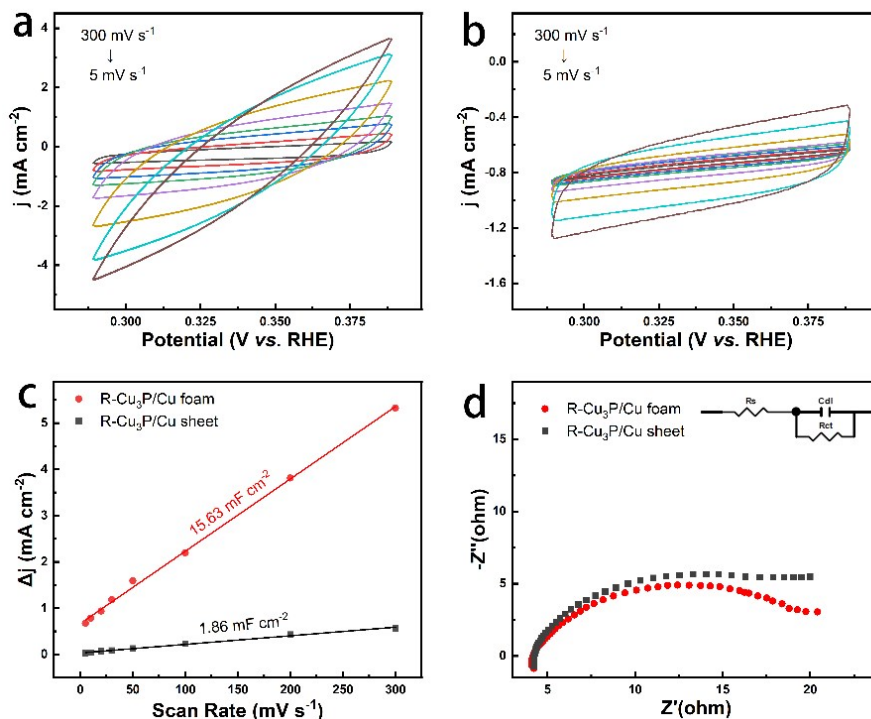


Fig. S18. CV curves of R-Cu₃P/Cu foam (a) and sheet (b) at different scan rates: 5, 10, 20, 30, 50, 100, 200, and 300 mV s⁻¹ from inside to outside. (c) Capacitive current at 0.339 V (vs. RHE) as a function of the scan rate for R-Cu₃P/Cu foam and sheet ($\Delta j = j_a - j_c$). (d) Nyquist plots of R-Cu₃P/Cu foam and sheet in the frequency range of 0.1-100 KHz. Inset: Randles' equivalent circuit used for fitting the experimental impedance data. Note: solution resistance (R_s), electrical double-layer capacitance (C_{dl}), charge transfer resistance (R_{ct}).

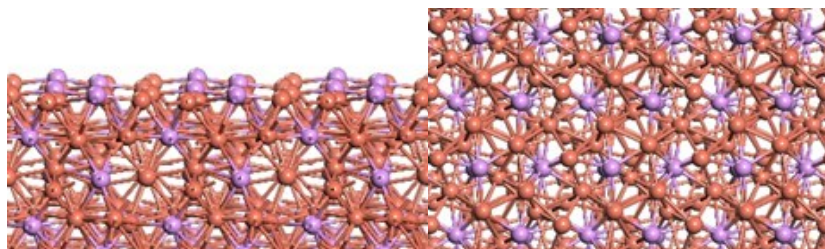


Fig. S19. Side and vertical view of the optimized structures of Cu₃P.

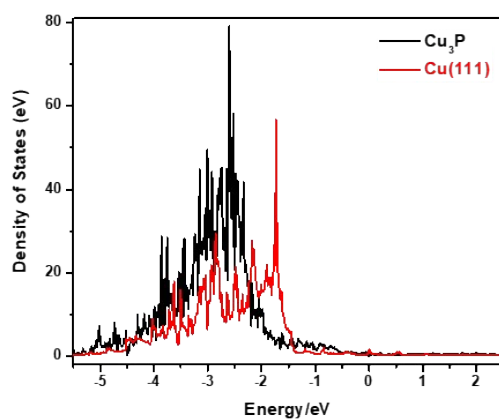


Fig. S20. DOS of d -electrons for the surface Cu atoms of Cu_3P and Cu (111) surface.

The energy is relative to the Fermi level.

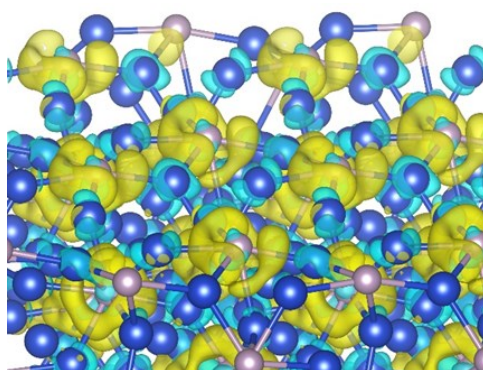


Fig. S21. Charge density difference of Cu and P on the bulk Cu_3P as defined by: $\Delta\rho = \rho_{\text{Cu}_3\text{P}} - \rho_{\text{Cu}} - \rho_{\text{P}}$. The yellow and green area represents electron accumulation and depletion, respectively.

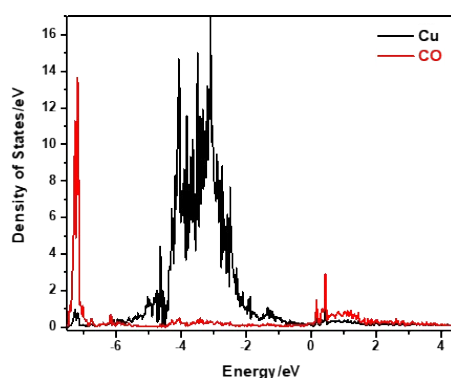


Fig. S22. DOS of d -electrons for the surface Cu atoms of Cu_3P and s, p -electrons for the adsorbed CO. The energy is relative to the Fermi level.

Table S1. Comparison with other reports on the CO₂RR to produce syngas.

Catalyst	Electrolyte	Current density (mA cm ⁻²) (CO/H ₂)	Tuneable ratio CO/H ₂	Stability (h)	Ref.
AgP ₂ nanocrystals	0.5 M KHCO ₃	0.28 (1:3) 2.46 (1:1)	1:3-5:1	12	(1)
Ag doped Co ₃ O ₄	0.1 M KHCO ₃	~ 7 (1:3)	1:4-5:4	10	(2)
silver nanowires	0.5 M KHCO ₃	4 (1:1) 22 (3:2)	1:1-4:1	12	(3)
Ru (II) polypyridyl	0.5 M NaHCO ₃	2.5 (1:4)	1:4-2:1	2	(4)
MoSeS alloy	4 mol% EmimBF ₄ 96 mol% H ₂ O	-	1:1	10	(5)
Zn _x Cd _{1-x} S- Amine	0.5 M NaHCO ₃	~ 6 (1:1)	0-19.7	10	(6)
Co and Ni Single-Atom	0.5 M KHCO ₃	> 74	0.23-2.26	7	(7)
Pd/C	0.5 M NaHCO ₃	0.3 (3:4)	1:4-3:4	-	(8)
γ-In ₂ Se ₃	30 wt% [Bmim]PF ₆ 65 wt% MeCN 5 wt% H ₂ O	90.1 (1:1)	1:3-24:1	25	(9)
SnO ₂ /CuS	0.1 M KHCO ₃	~5 (1:1) ~3 (1:3)	0.11-3.86	24	(10)
Zn-Ni	0.1 M KCl	8.4 (11:9)	-	50	(11)
Au/TiNS	0.5 M KHCO ₃	-	0.3-3	-	(12)
PdH/TMN	0.5 M NaHCO ₃	0.4 (3:4)	0.16-0.74	-	(13)
CdS _x Se _{1-x} nanorods	0.1 M KHCO ₃	27.1	1:4-4:1	10	(14)
Co ₃ O ₄ -Cdots C ₃ N ₄	0.5 M KHCO ₃	0.25 (1:1)	0.07:1-4:1	30	(15)

MoS ₂	EMIM-BF ₄ solution (94 mol% water)	61 (4:1)	1:2-4:1	10	(16)
Zn	0.1 M KHCO ₃	11.36 (7:6)	1:5-2.31:1	9.5	(17)
Fe-N-C	0.5 M NaHCO ₃	-	0-4:1	10	(18)
Cu-enriched Au	0.5 M KHCO ₃	30 (1:1)	-	8	(19)
Cu-In alloys	0.1 M KHCO ₃	-	1:18-1:2.6	16.7	(20)
Cu	0.1 M KHCO ₃	~7 (1:1)	9:16-32:1	-	(21)
carbon- supported Cu/In ₂ O ₃	0.5 M KHCO ₃	4.6 (1:4) 12.7(1:0.4)	1:4-1:0.4	5	(22)
R-Cu ₃ P/Cu	0.5 M NaHCO ₃	36.3 (1:1) 82.9 (1:2) 115.0 (2:5) 130.0 (1:3)	0.1-2.24	> 20	This work

Table S2. Bader charge for the surface atoms of Cu₃P.

Atom	P	P	Cu	Cu	Cu	Cu	Cu	Cu
Charge	-0.56	-0.56	0.19	0.17	0.17	0.19	0.20	0.20

Table S3. Bader charge of CO₂ chemisorption on Cu₃P surface.

Atom	C	O	O	Tot
Charge	1.58	-1.08	-1.06	-0.56

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